



SHEET 1 OF 2

INFORMATION DISCLOSURE
CITATION IN AN
APPLICATION

(PTO-1449)

ATTY. DOCKET NO.
055071-0328

SERIAL NO.
10/756,829

APPLICANT
Robert John SOCHA, et al.

FILING DATE
January 14, 2004

GROUP
2825

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/Suresh Memula/

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